

# Effects of 2 MeV Ge<sup>+</sup> Irradiation on AlGaN/GaN High Electron Mobility Transistors

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# Outline

- Background
- Radiation Simulations
- Affect on:
  - DC device characteristics
  - Affect on Schottky Gate
  - Isolation/TLM structures
- Off-state stress
- Conclusions

# Background

- GaN radiation hardness surpasses GaAs due to higher binding energy of GaN.
- Results in reduced radiation defects in GaN.
- Many studies performed on effect of protons and  $\alpha$ -particles on GaN device performance.
- Earth's magnetosphere composed of:
  - 85% protons
  - 14%  $\alpha$ -particles
  - 1% heavy ions
- Solar flares can result in heavy ion irradiation up to several hundred MeV.

# Proton Irradiation

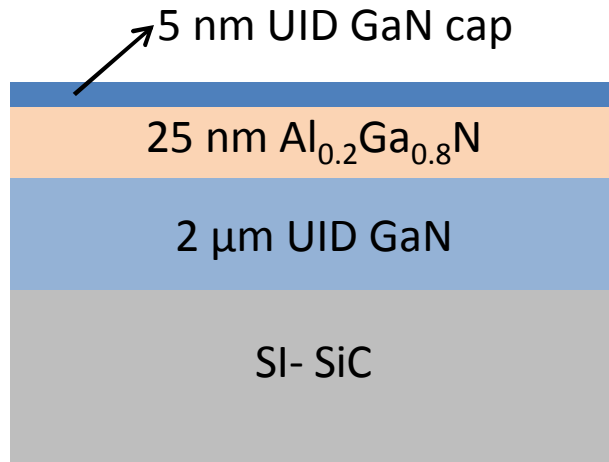
- Carrier removal rate  $\sim 10^2 - 10^3 \text{ cm}^{-1}$
- Deep trap formation with  $E_A = 0.13, 0.16-0.18, 0.2-0.21 \text{ eV}$ .
- At high proton doses, aggregates of primary defects can form, resulting in electron traps with  $E_A = 0.75$  and  $0.95 \text{ eV}$
- Deep electron traps result in increase of channel resistance.

# Electron Irradiation

- Primary defect in GaN from electron irradiation is N vacancies.
- Results in  $E_A = 0.16-0.18 \text{ eV}$

# AlGaN/GaN HEMT

## MOCVD epitaxial layers



## Device Structure

Ohmic Contacts: Ti/Al/Pt/Au

Schottky Gate: Ni/Au

Gate length: 1μm

Gate width: 100μm

Both HEMT and TLM structures tested

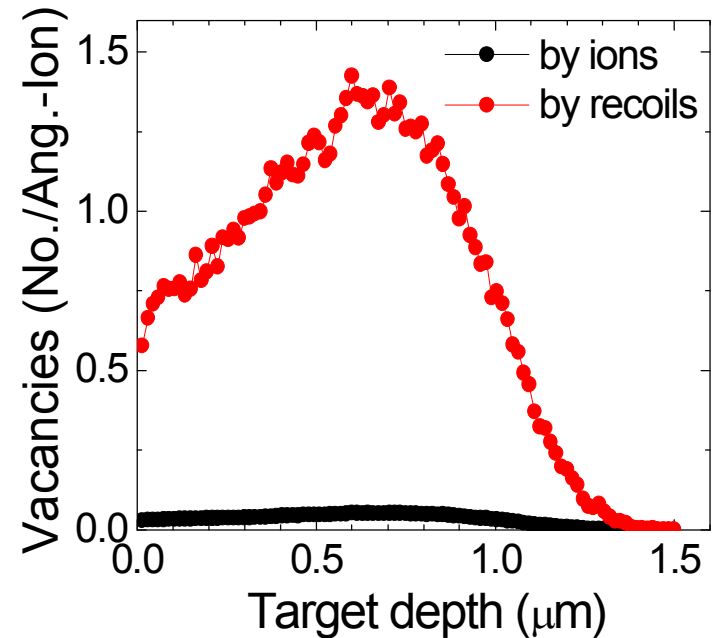
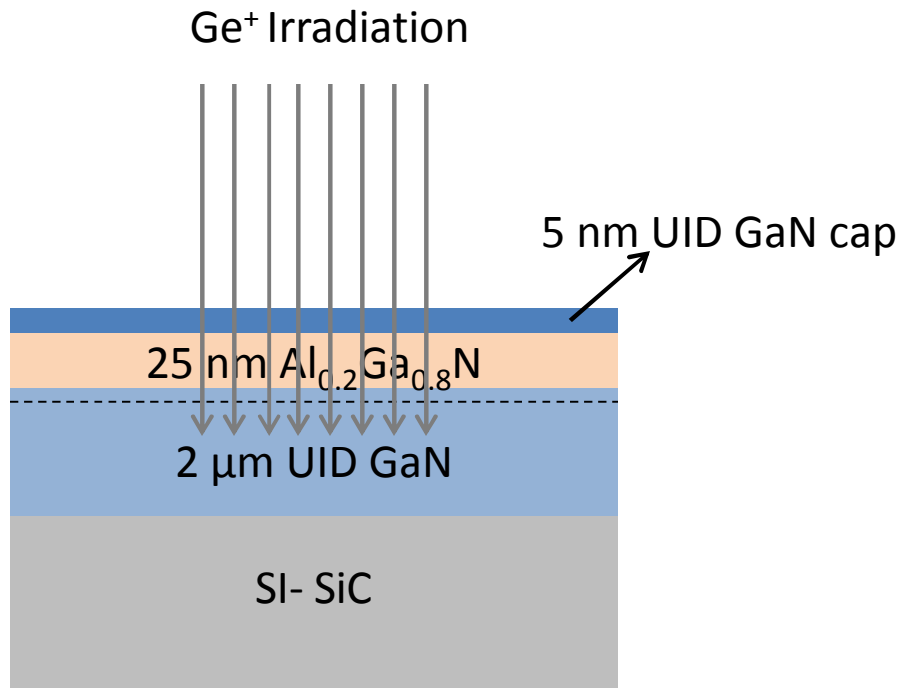
## Heavy Ion Irradiation

2 MeV Ge<sup>+</sup>

Dose range:

$5 \times 10^{10}$  to  $5 \times 10^{12}$  cm<sup>-2</sup>

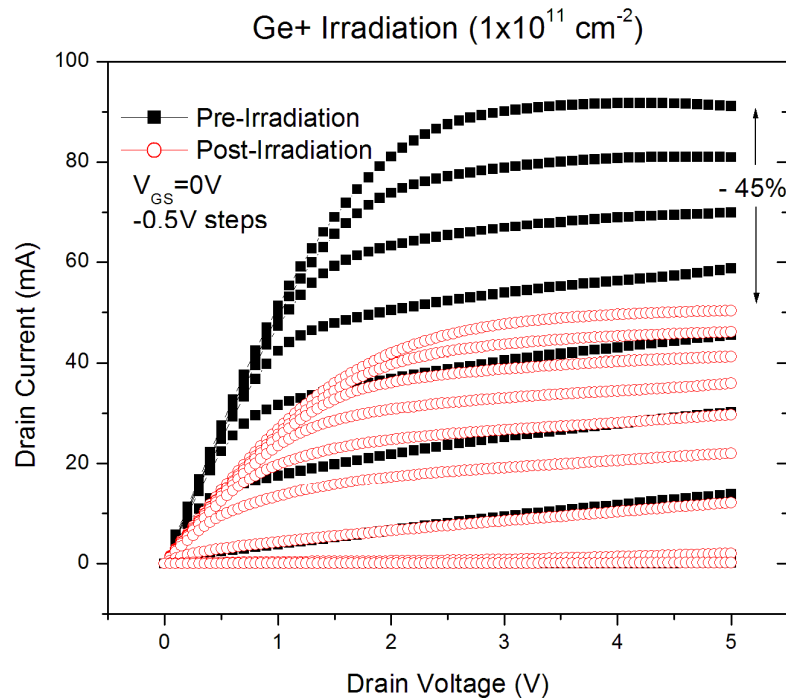
# SRIM Simulations



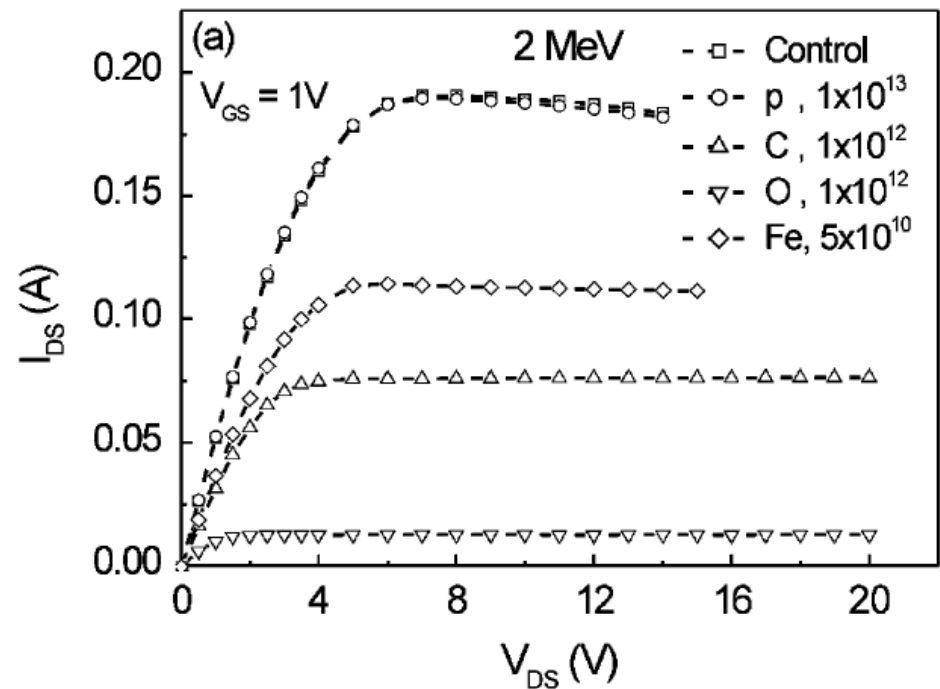
Stopping Range of Ions in Matter (SRIM) simulation indicates end of range of ions ~0.65 μm in HEMT structures.

➤ In GaN buffer below active layers

# AlGaN/GaN HEMT Performance

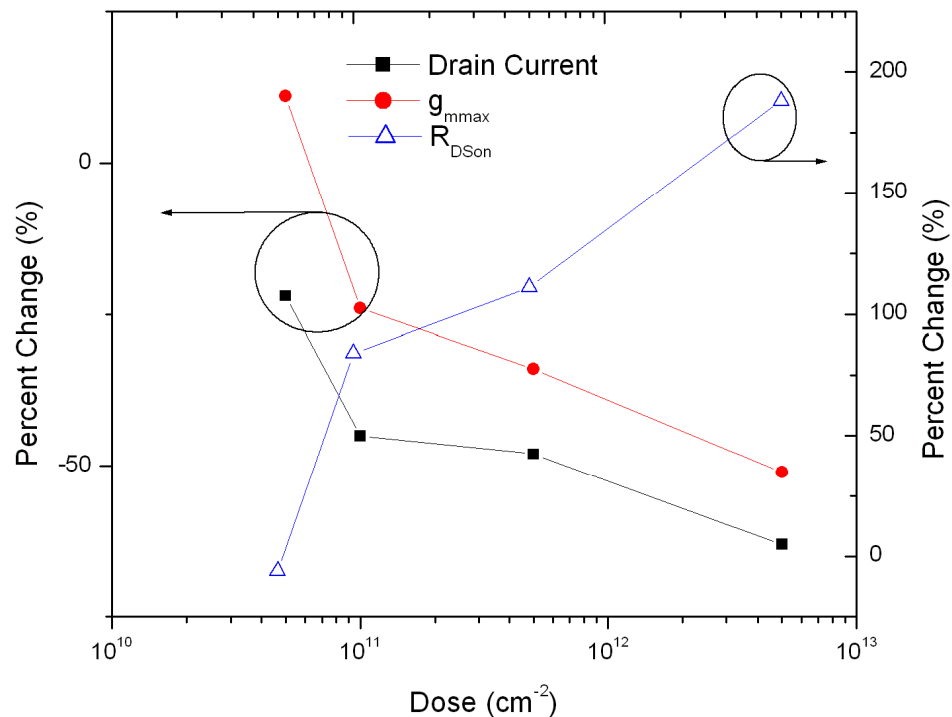


~45% drop in  $I_{DSS}$ , consistent with other heavy ion irradiation



Sonia, G. et al., *Nuclear Science, IEEE Transactions on*, **53**, 3661 (2006).

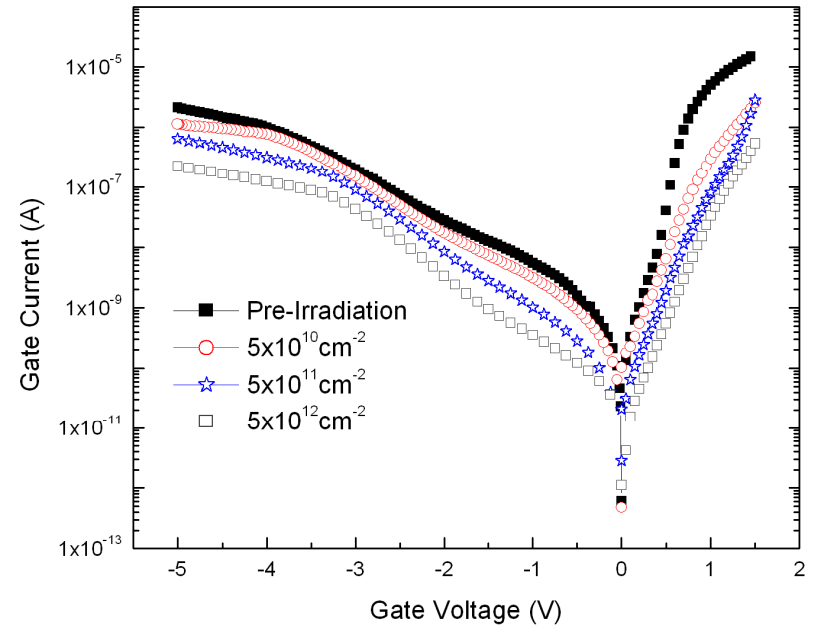
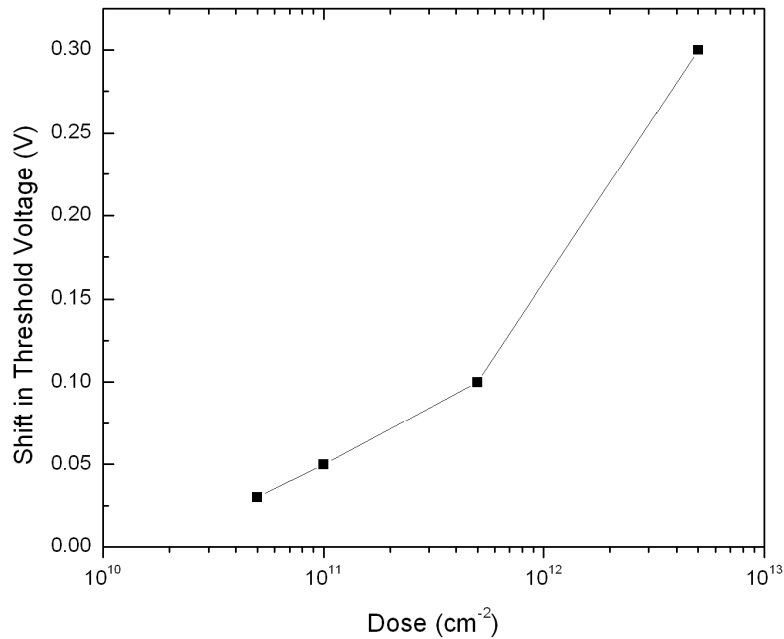
# AlGaN/GaN HEMT Performance (2)



- Decrease in transconductance and drain current.
- Increase in source-drain resistance.
- Consistent with carrier removal from channel.
- Drain current not linear, tends toward saturation.
- Expected trend if number of deep traps approaches carrier density of channel.

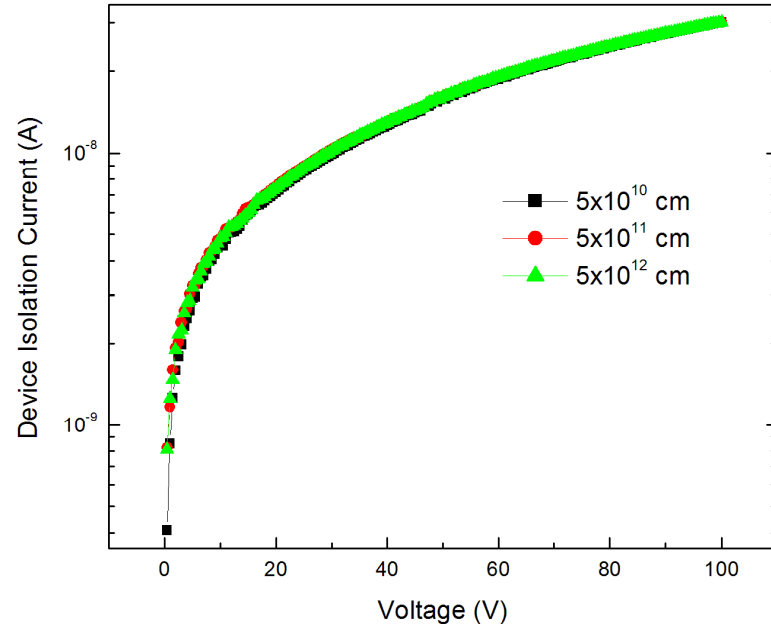
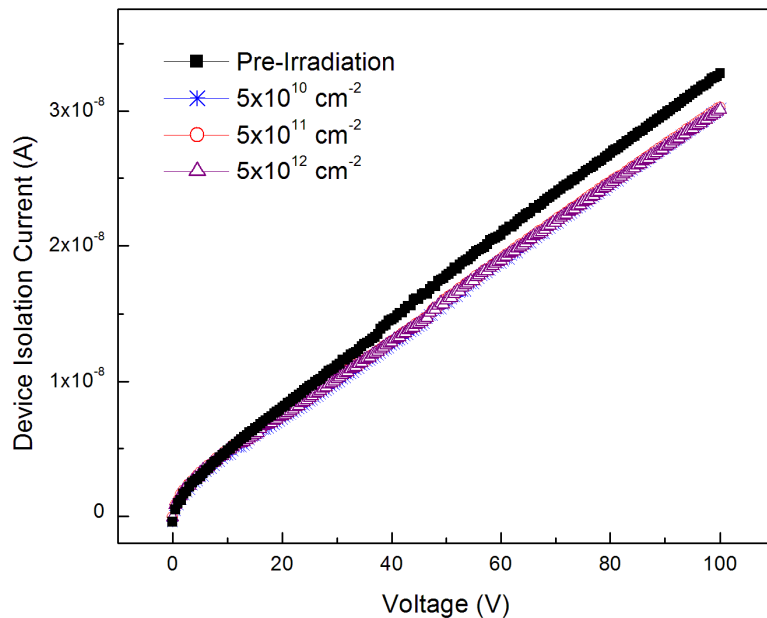


# Schottky Gate



Substantial shift in  $V_{TH}$  observed with dose.  
Decrease in gate leakage current with increase in dose.

# Isolation Current



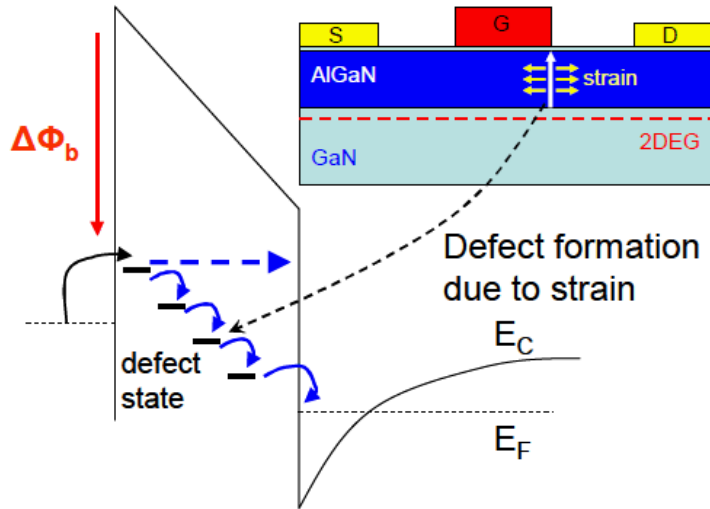
**Decrease in isolation current. However, no trend with  $\text{Ge}^+$  dose.**

TLM irradiated with  $5 \times 10^{10} \text{ cm}^{-2}$  resulted in:

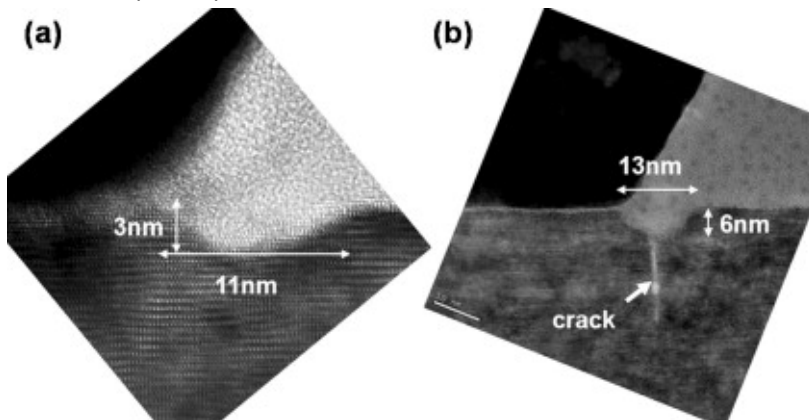
- ~4X increase in sheet resistance
- 75% decrease in specific contact resistance.

**Consistent with carrier removal from channel of HEMT**

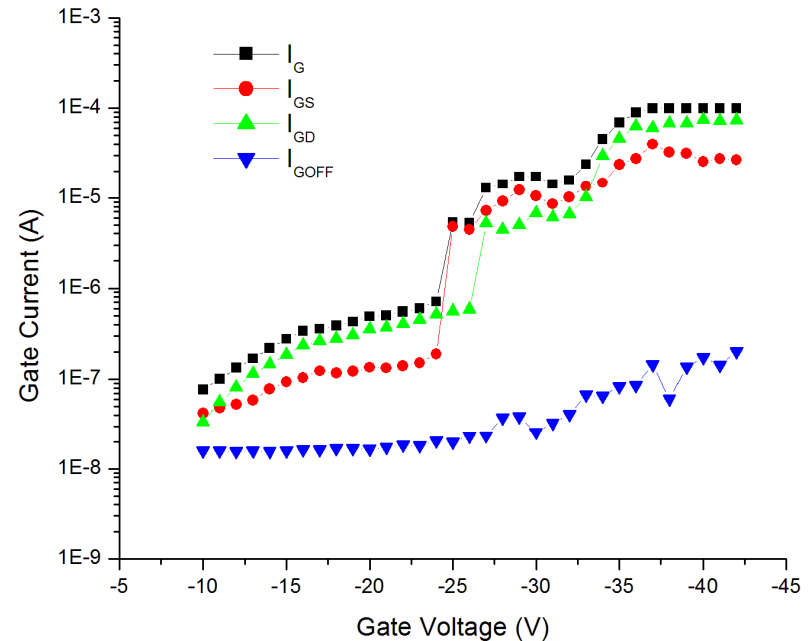
# Off-State Stress



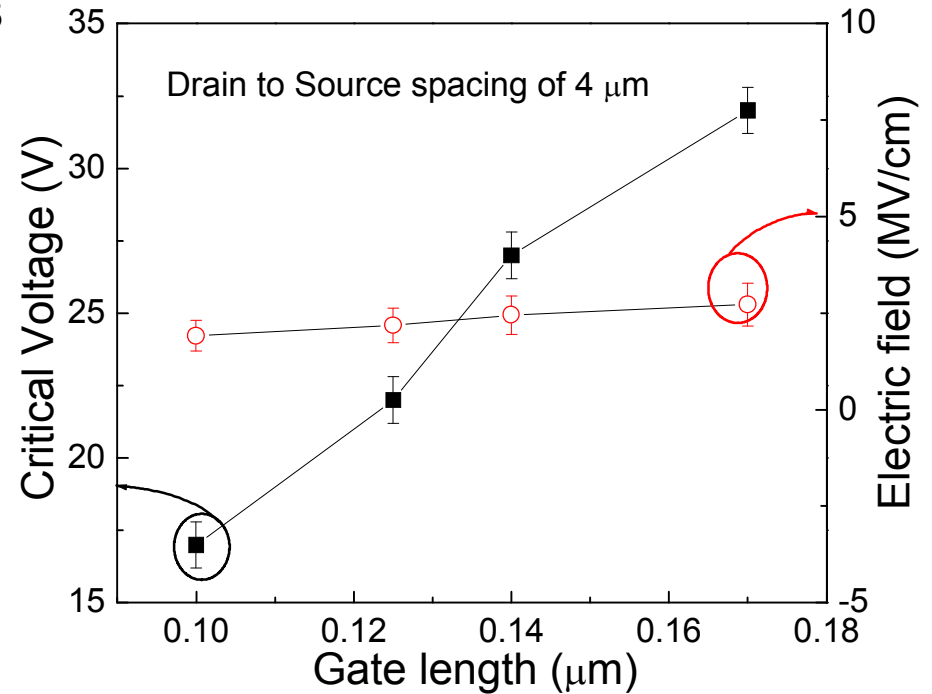
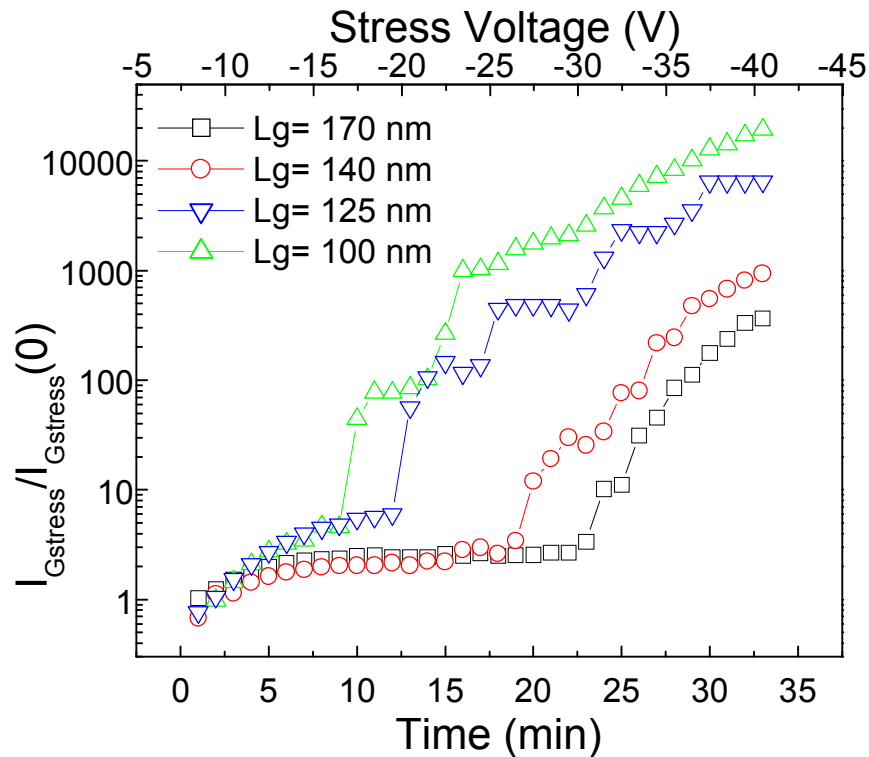
J. A. del Alamo, J. Joh. Microelectronics Reliability, 49 1200, (2009).



Park, et al. Microelectronics Reliability 49 (5) 478, (2009).

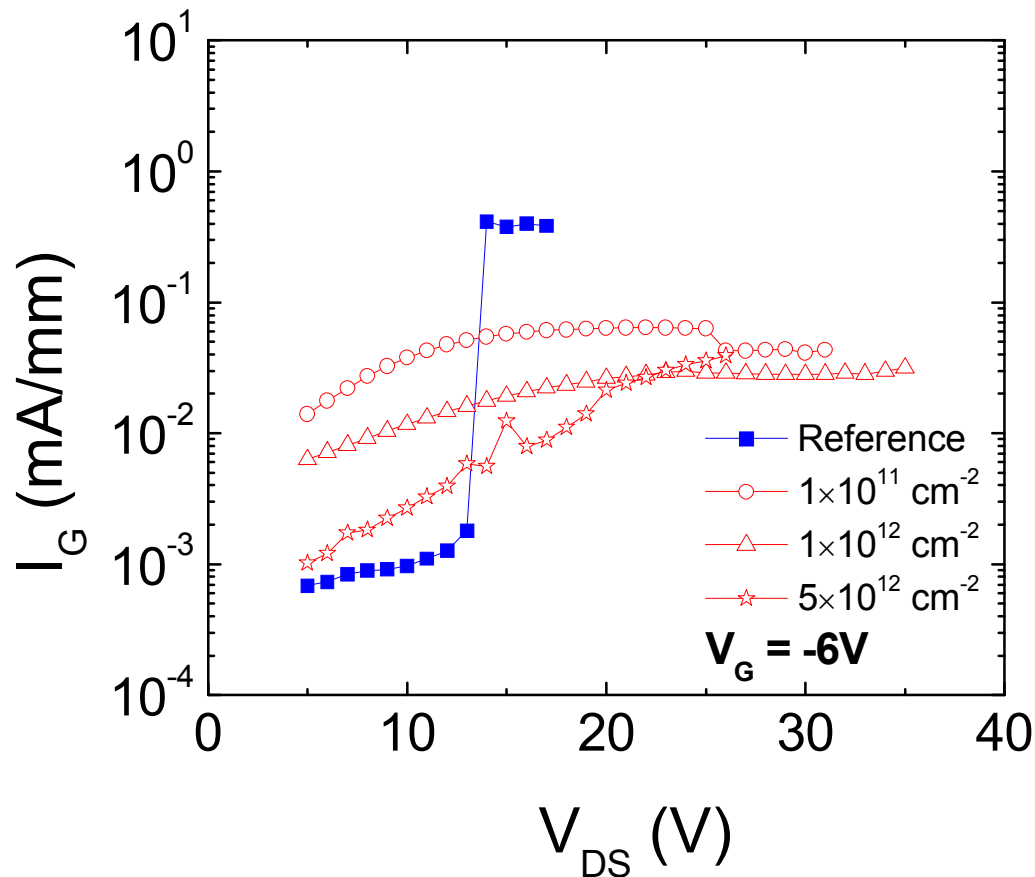


# Off-State Stress (2)



Breakdown occurs at  $\sim 1.8$  MV/cm independent of gate length

# Off-State Stress (3)



- Typical  $V_{cri}$  ranges from 13 V to 15 V (believed to be field driven mechanism).
- No breakdown observed for  $\text{Ge}^+$  irradiated devices, up to 35 V.
- Similar results observed for proton irradiated devices.
- Defects due to ion irradiation effects electric field distribution near the gate.

# Conclusions

- Significant improvement of reliability of AlGaN/GaN HEMTs for 2 MeV Ge<sup>+</sup> irradiation.
- Critical voltage for off-state electrical stress increased from 13 V to above 35 V.
- Gate current decreased by about half after irradiation at  $10^{11}$  cm<sup>-2</sup>, indicating significant device degradation as compared to protons.

# Acknowledgements

Sandia National Laboratories is a multi-program laboratory managed and operated by Sandia Corporation, a wholly owned subsidiary of Lockheed Martin Corporation, for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-AC04-94AL85000. The work at UF is supported by HDTRA (Don Silversmith) under contract U.S. DOD HDTRA Grant No. 1-11-1-0020 and an AFOSR MURI monitored by Jim Hwang.